

Status of the Gallium Nitride High Electron Mobility Transistor Radiation Testing for the NEPP Program

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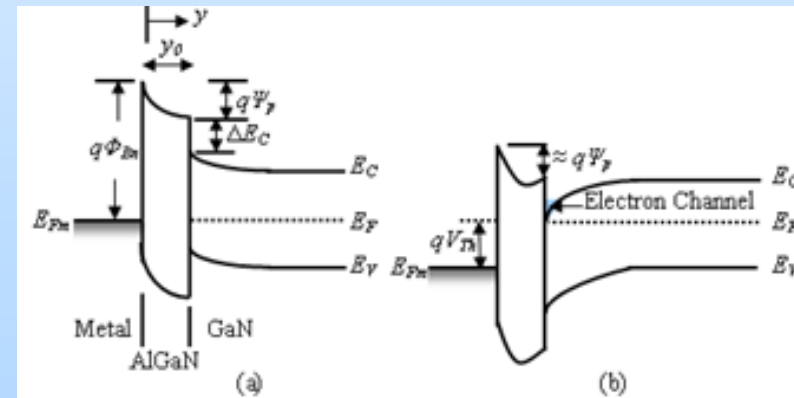
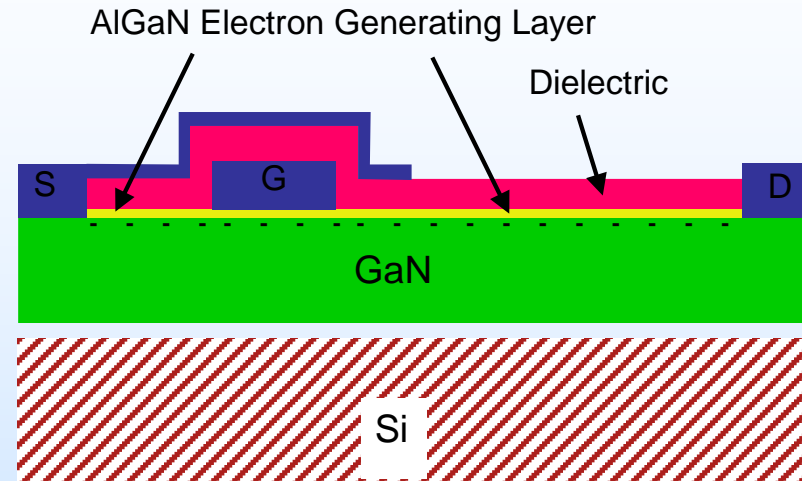


Current activities

- **Working group discusses best methods for evaluating new wide band gap technologies for infusion into space**
 - GRC, JPL, JSC, GSFC, AFRL
 - Monthly meeting to share data and resources for radiation effects testing and reliability analyses
- **Previous efforts have been broad stroke testing**
 - Heavy ion testing
 - Gallium Nitride HEMTs (JPL)
 - Silicon Carbide MOSFETs (GSFC)
 - Reliability screening
 - Temperature cycling of GaN and SiC
- **On going and future efforts**
 - Continues radiation testing and analysis
 - Reliability test screens for new devices
 - Guidelines for implementation and testing

GaN Basics

- **Current silicon power solutions are at their innate limits for space applications**
 - Silicon devices are at efficiency limit
 - Best hi-rel devices are less than ~400 V drain-to-source
- **GaN devices are becoming available**
 - Reliability effects are a concern
 - Gate stress is limited (abs max of V_{gs} +6, -5 V)
 - Thermal effects and aging are under study at GRC

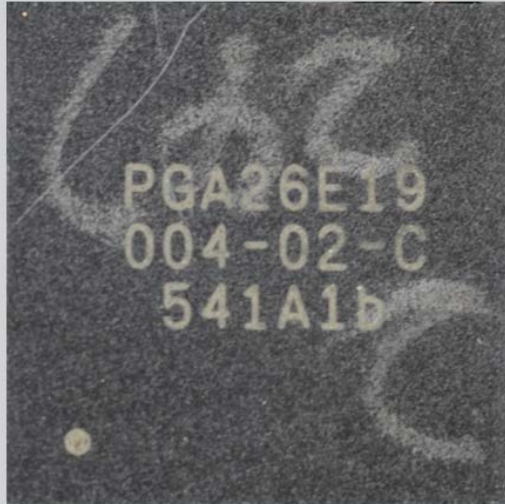




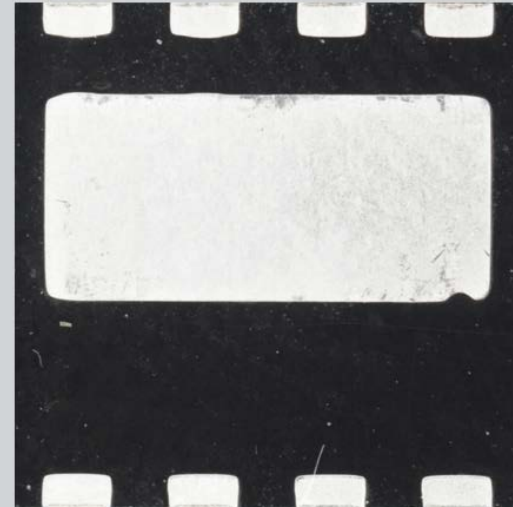
PGA26E19BA

TESTING OF PANASONIC PARTS - CONTINUED

Optical Images

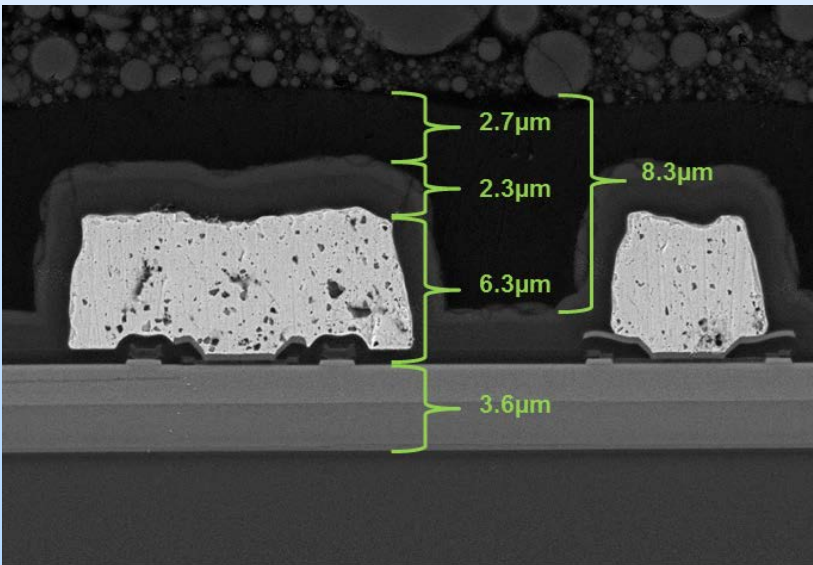
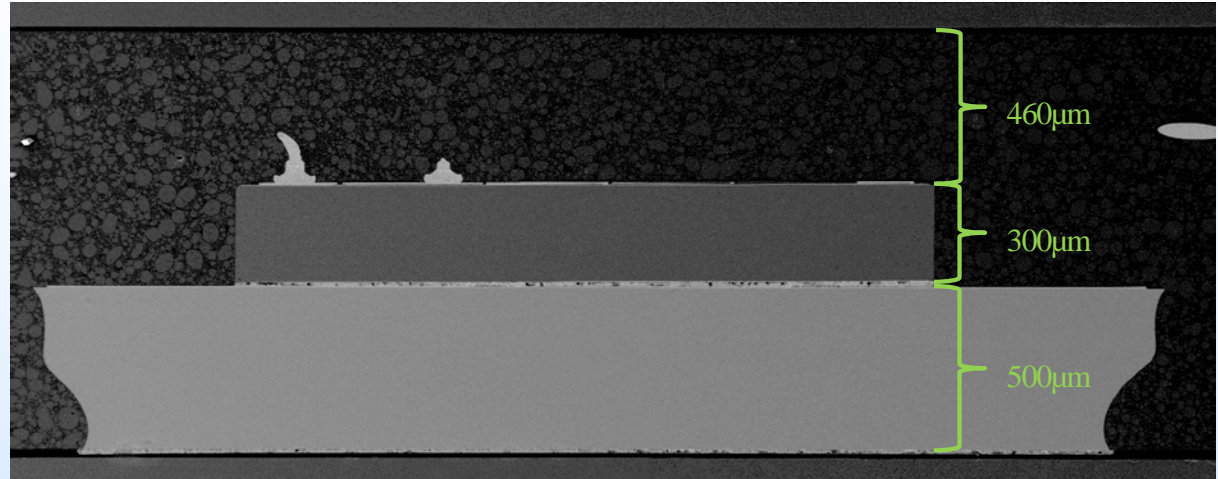


Front



Back

Accomplishments

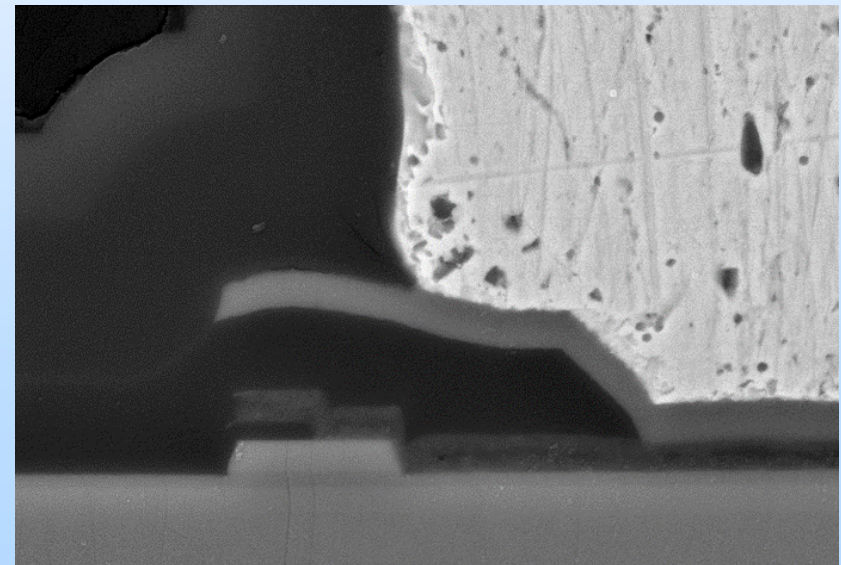


1 μ m
EHT = 10.00 kV
WD = 7.1 mm
Signal A = SEI
Mag = 3.15 K X
Date :26 Apr 2016
FIB Lock Mags = No



agin

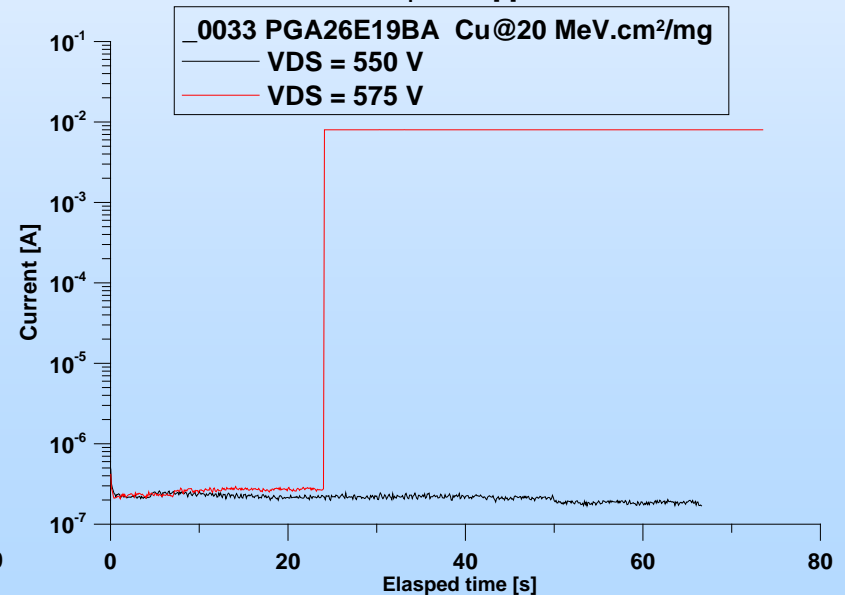
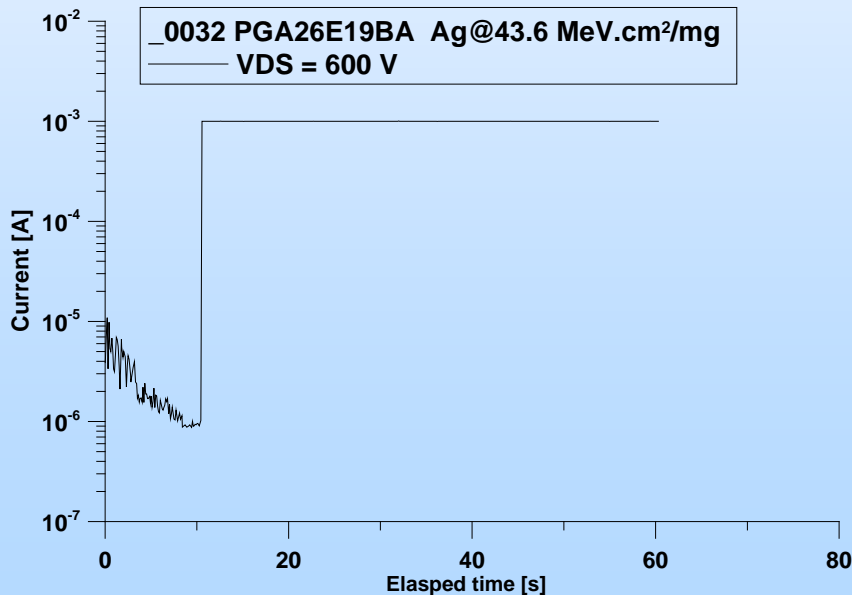
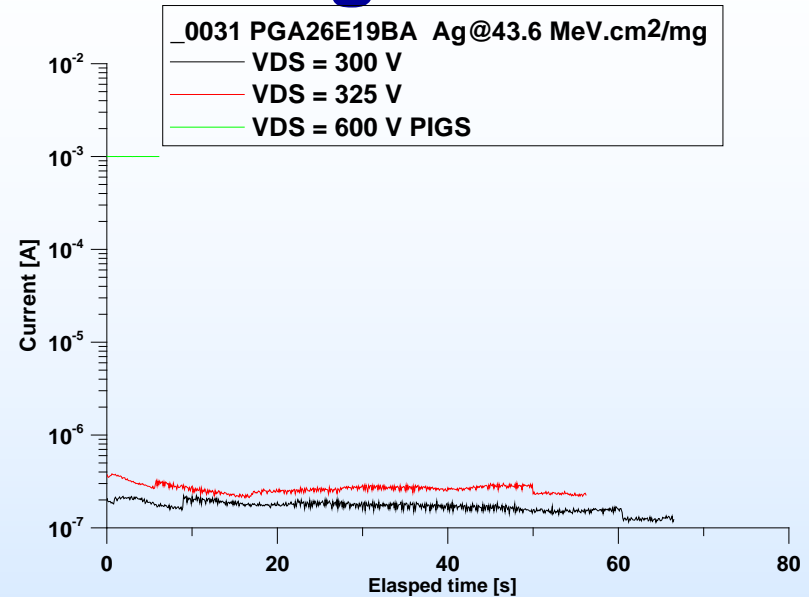
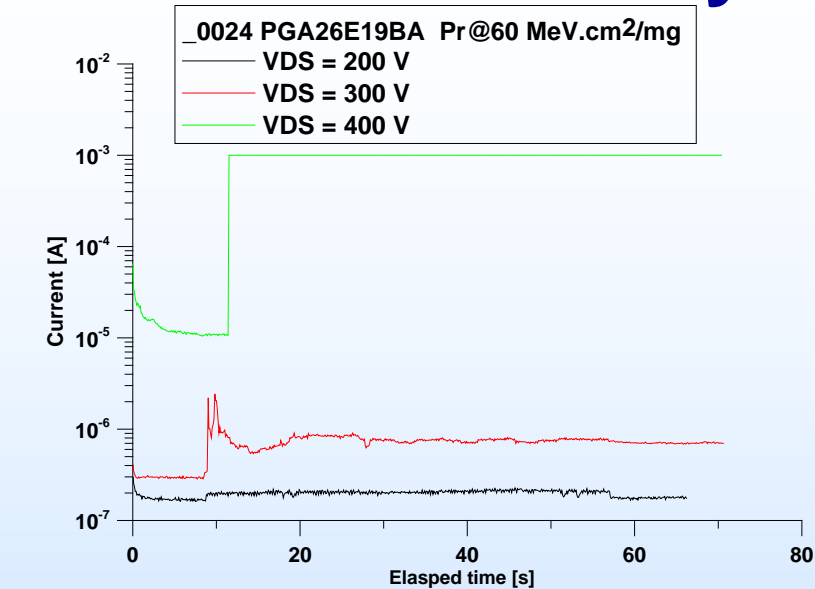
NASA GSFC, Greenbelt, MD.



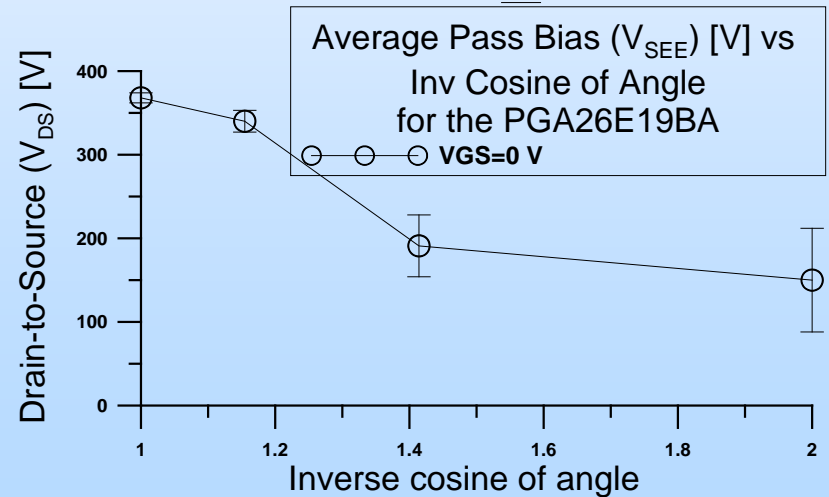
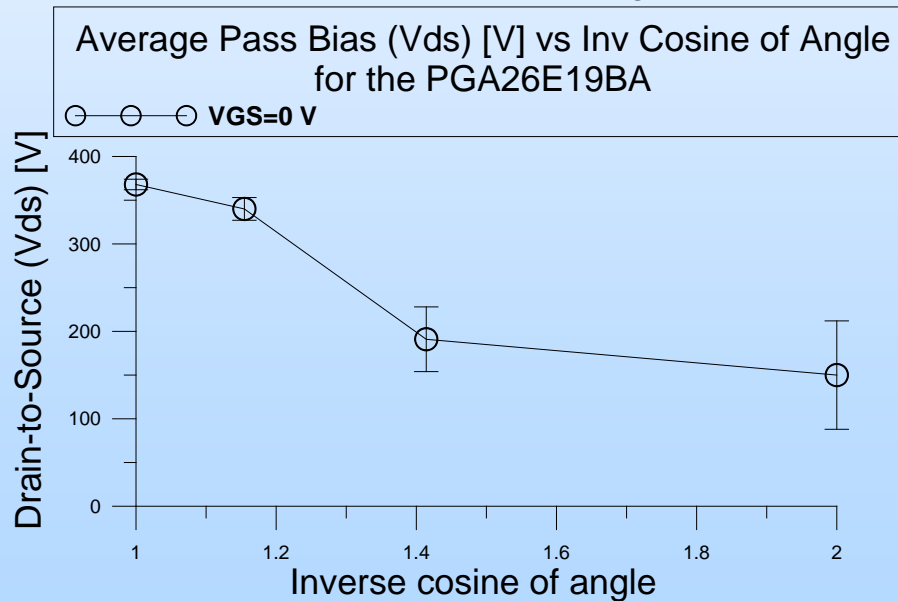
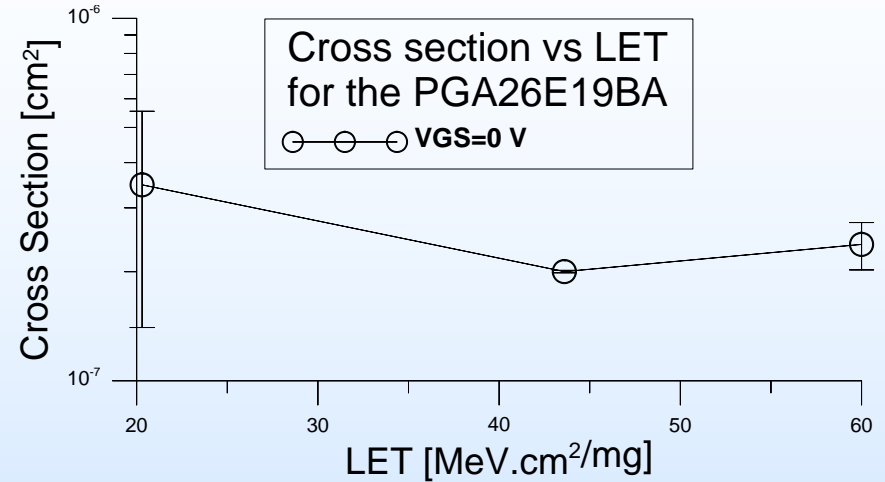
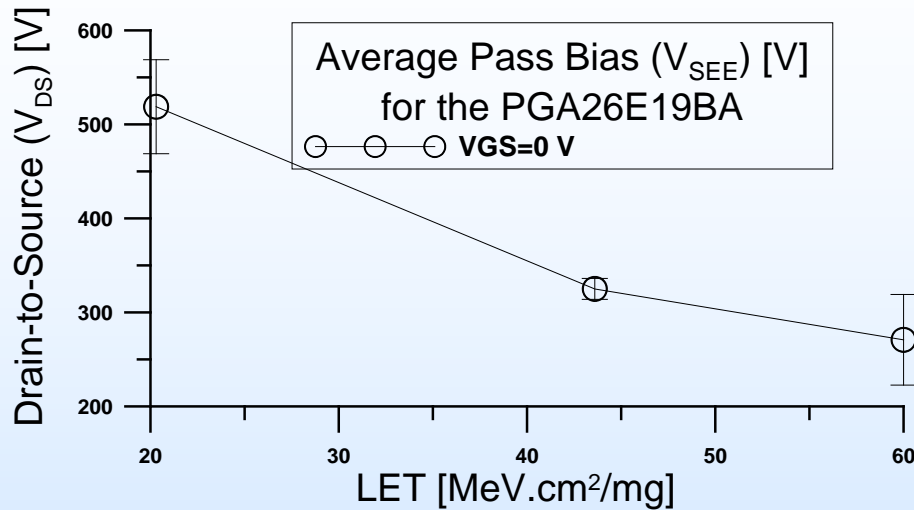
200 nm
EHT = 10.00 kV
WD = 7.1 mm
Signal A = SEI
Mag = 20.00 K X
Date :26 Apr 2016
FIB Lock Mags = No



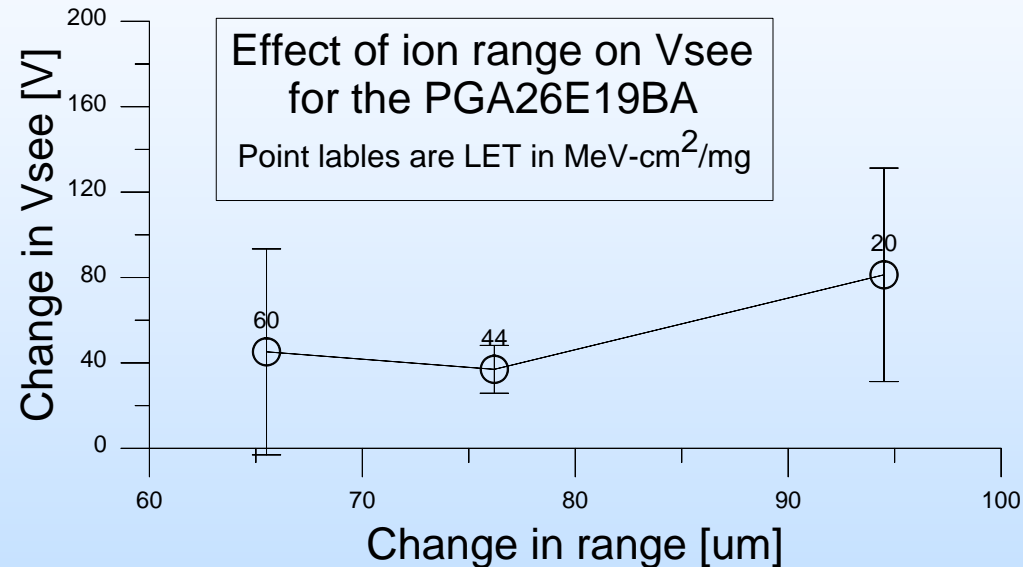
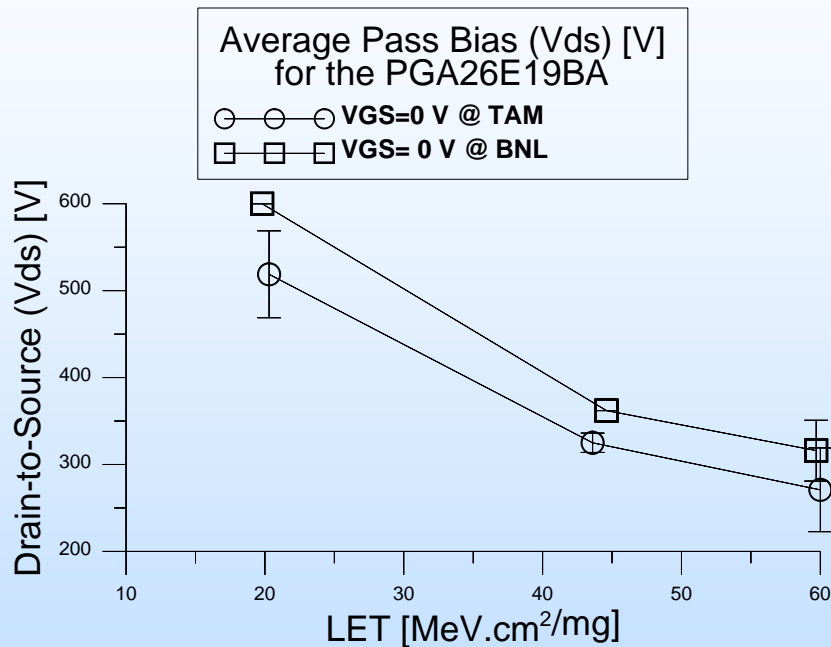
Heavy Ion Testing



Heavy Ion Testing

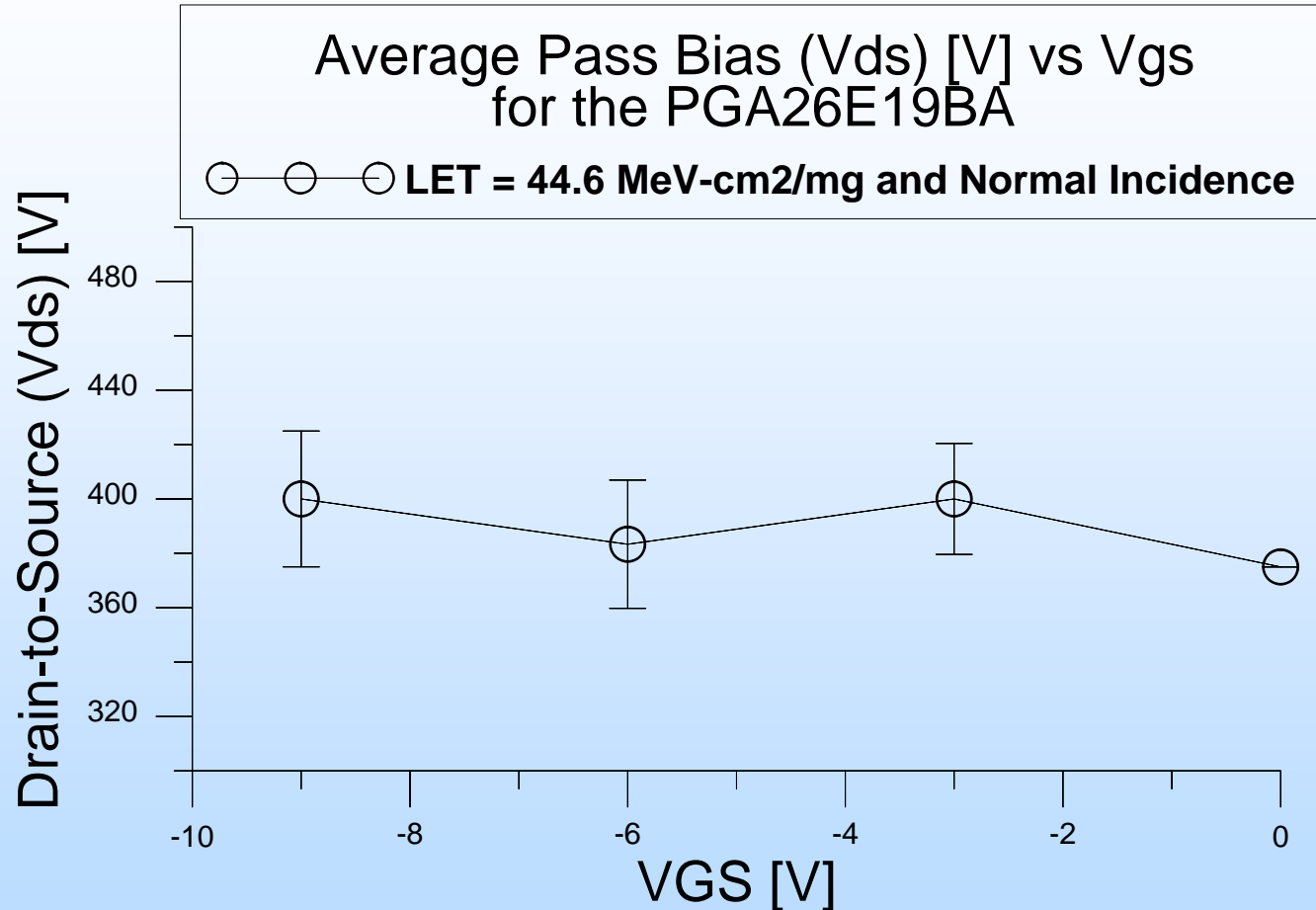


Heavy Ion Testing



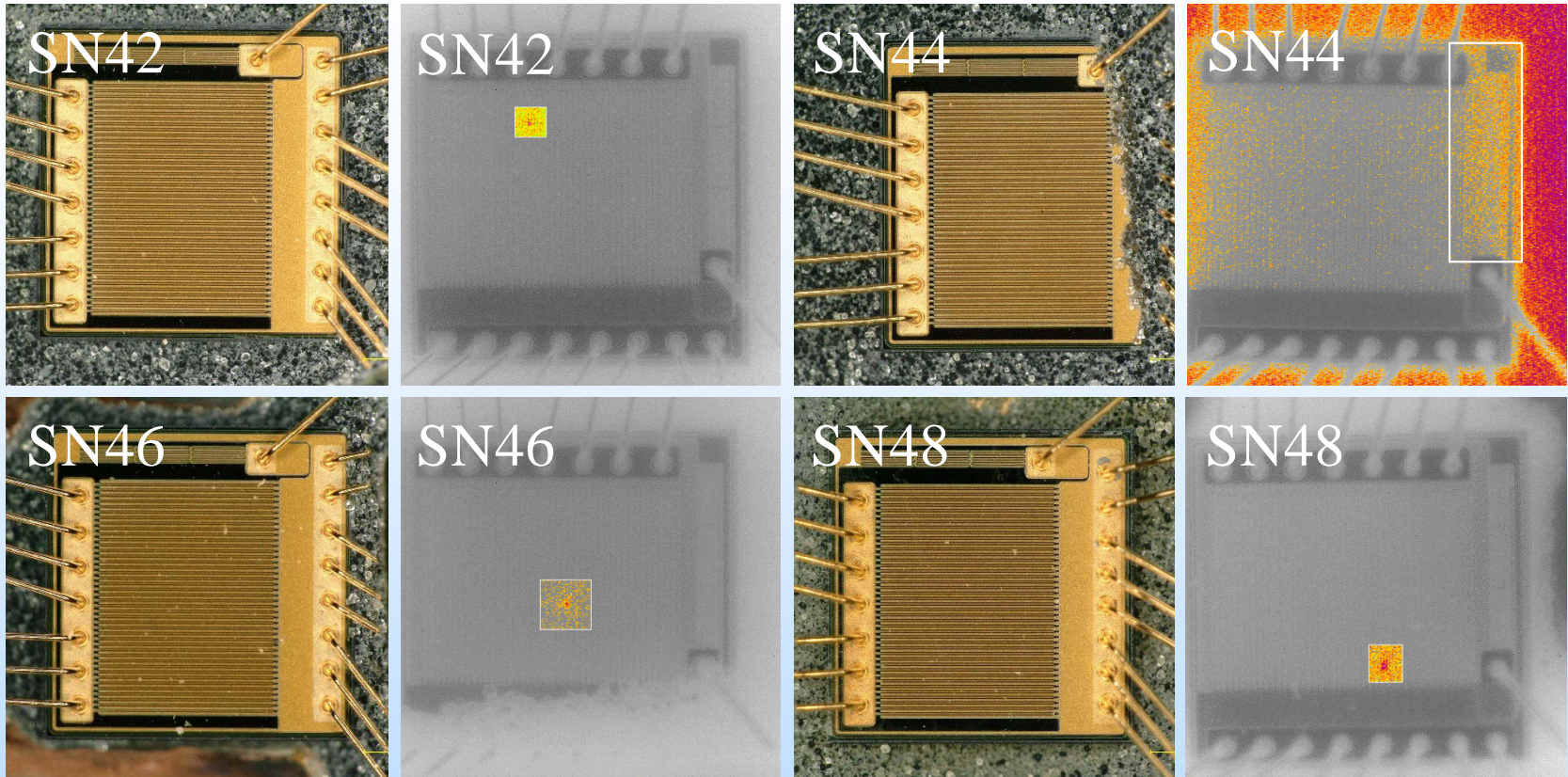
Deeper ion penetration decreases Vsee

Heavy Ion Testing



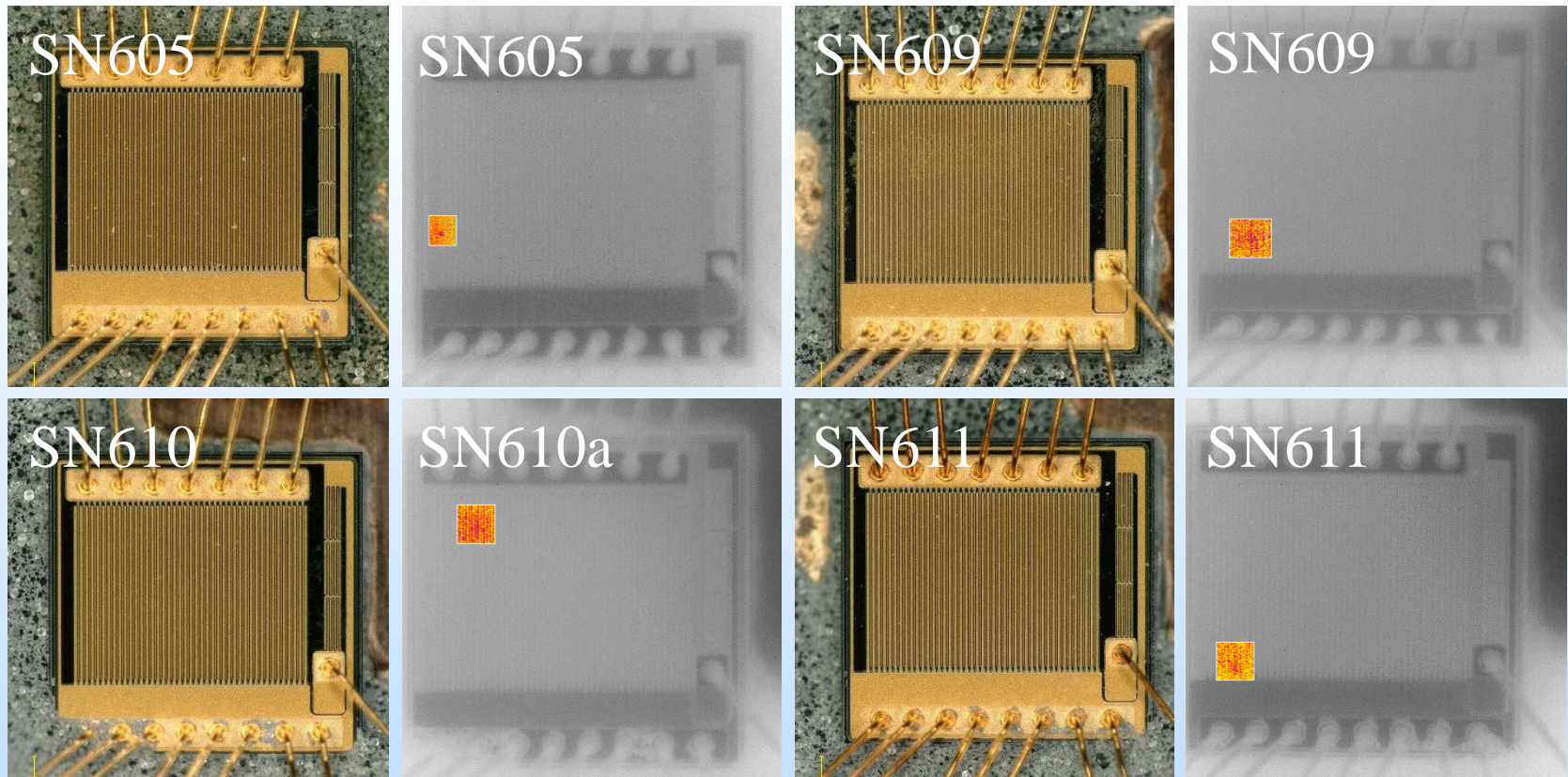
Gate-to-source voltage has no effect on V_{see}

Optical and Infrared Images with Hot Spots



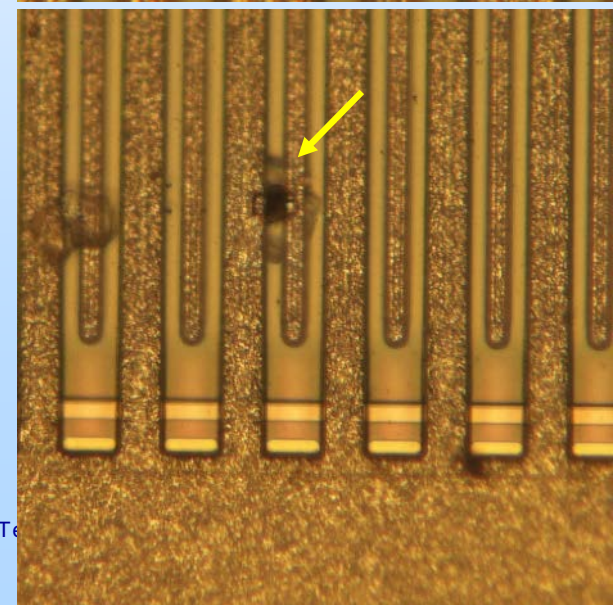
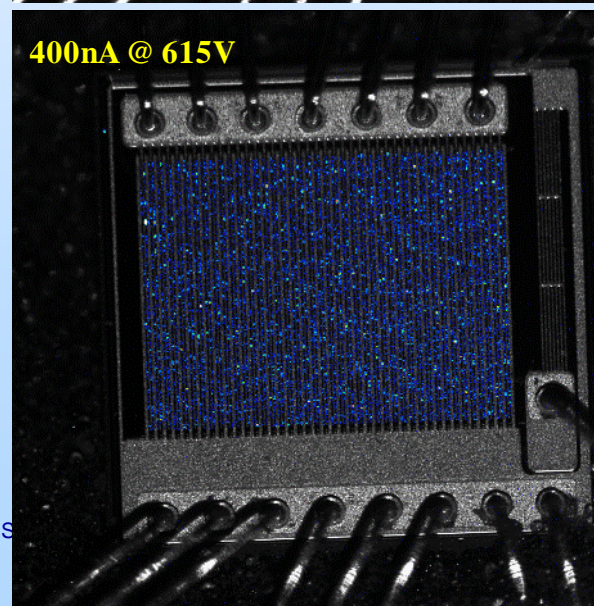
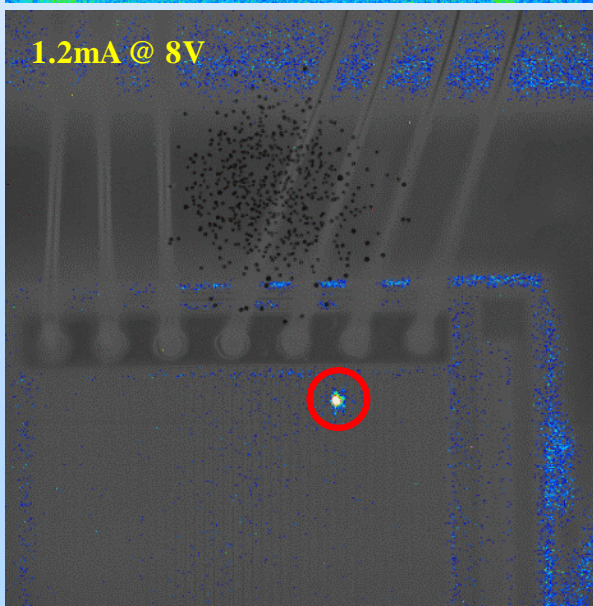
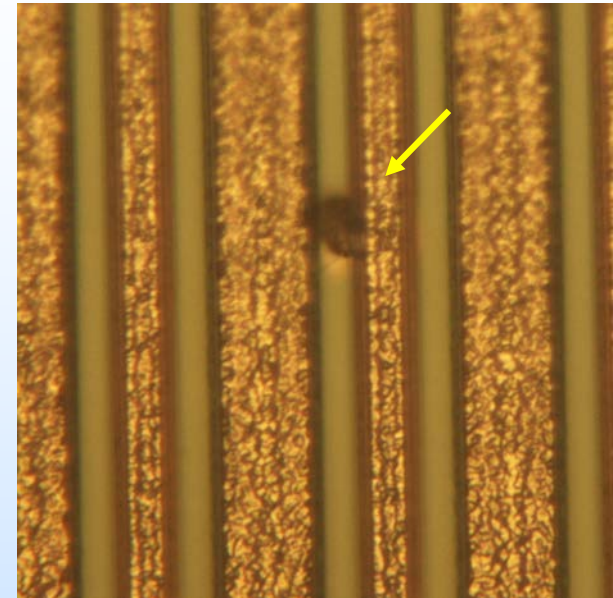
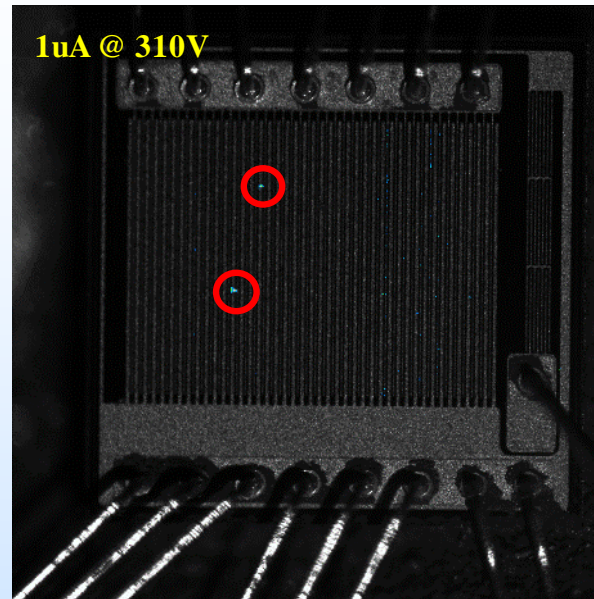
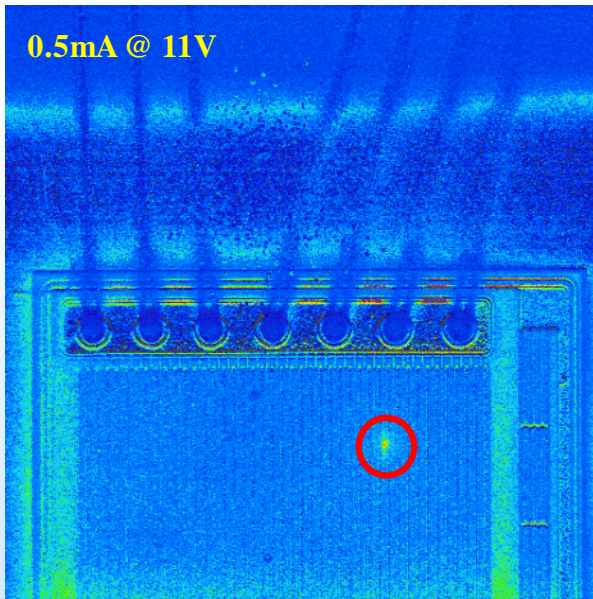
- Hot spot in boxed region

Optical and Infrared Images with Hot Spots



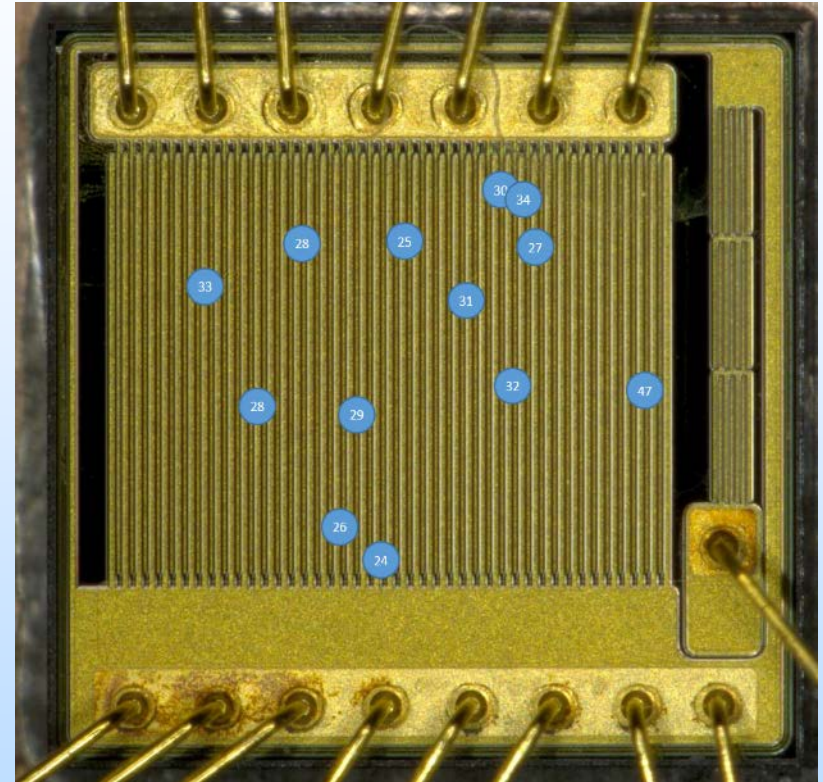
- Hot spot in boxed region

Failed Die Analysis



SEE population

- SEE on this devices are very telling
- They all occur on the gate
- It appears that all are on the drain side although damage is quite large
- Randomly dispersed



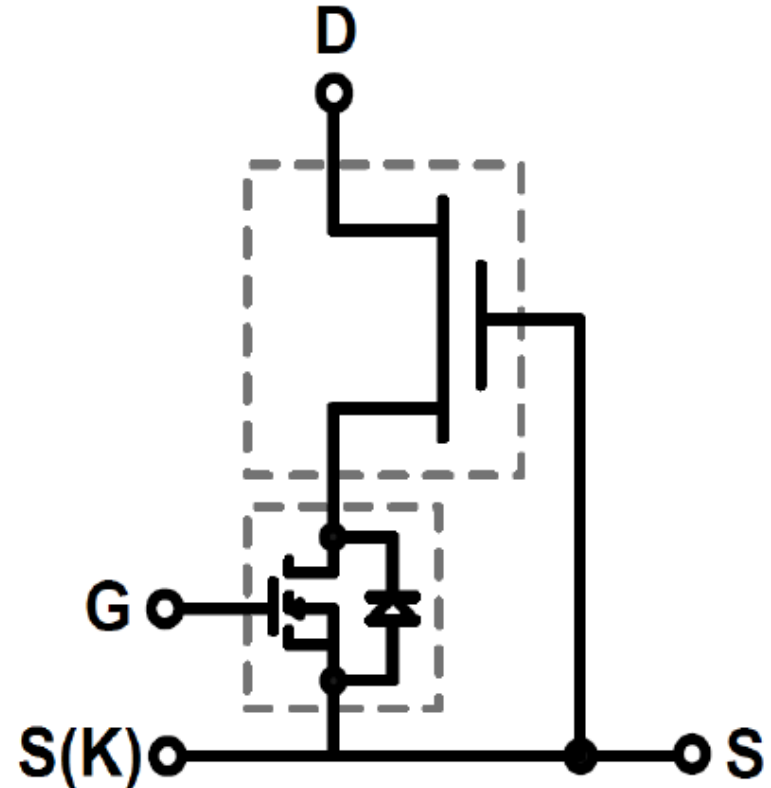


TPH3208 and TPH3202

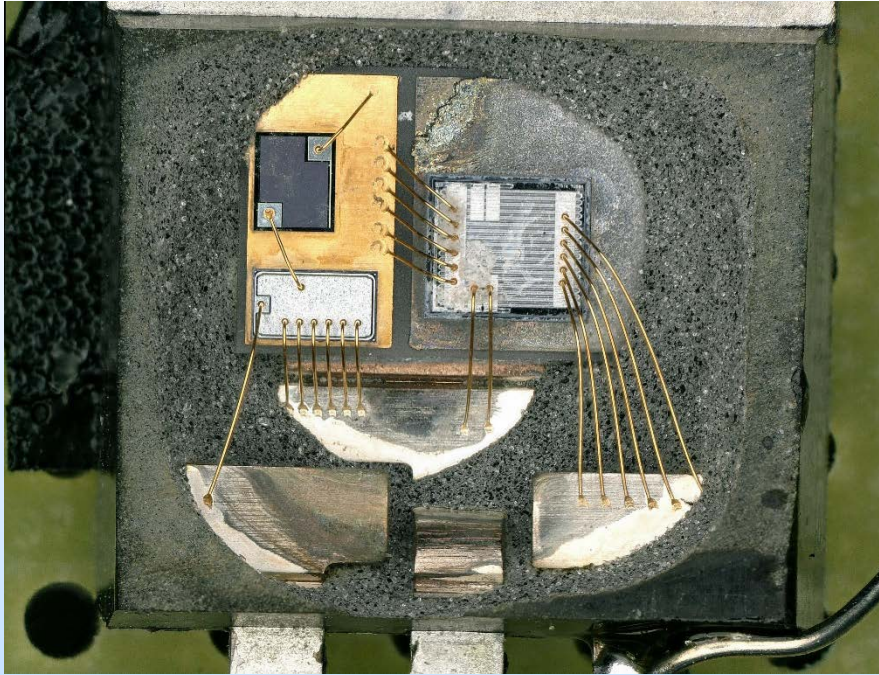
TESTING OF TRANSPHORM CASCODE HYBRIDS

Cascode Hybrids

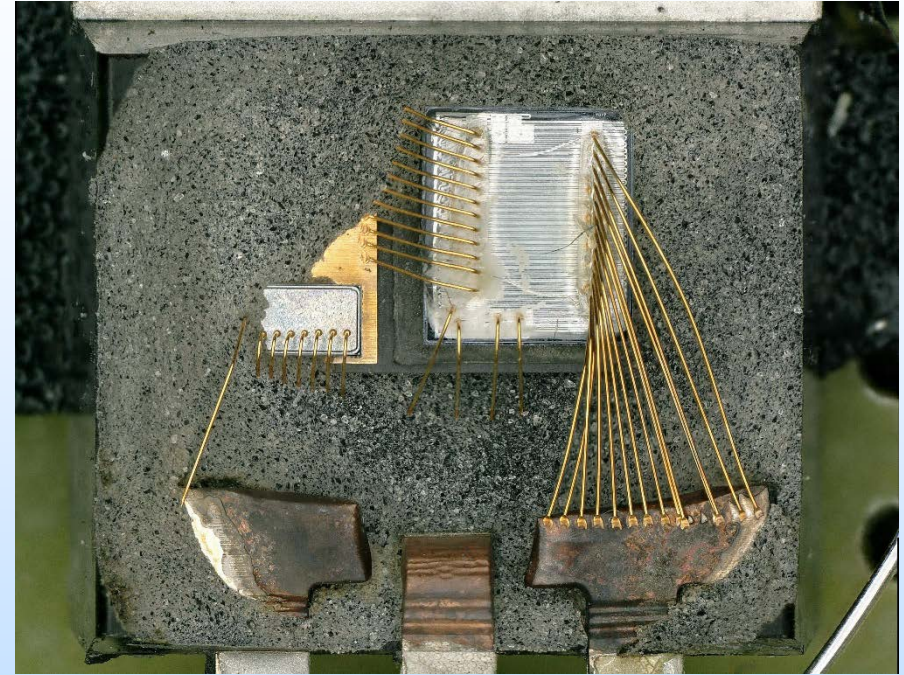
- **Cascode configuration allows for a depletion mode HEMT ($V_{th} < 0\text{ V}$) to emulate an enhancement mode FET ($V_{th} > 0\text{ V}$)**
- **Advantages are high gain, high bandwidth, high slew rate, high stability, and high input impedance**
- **Disadvantage is being a hybrid the device may be hard to assure**



Optical Images

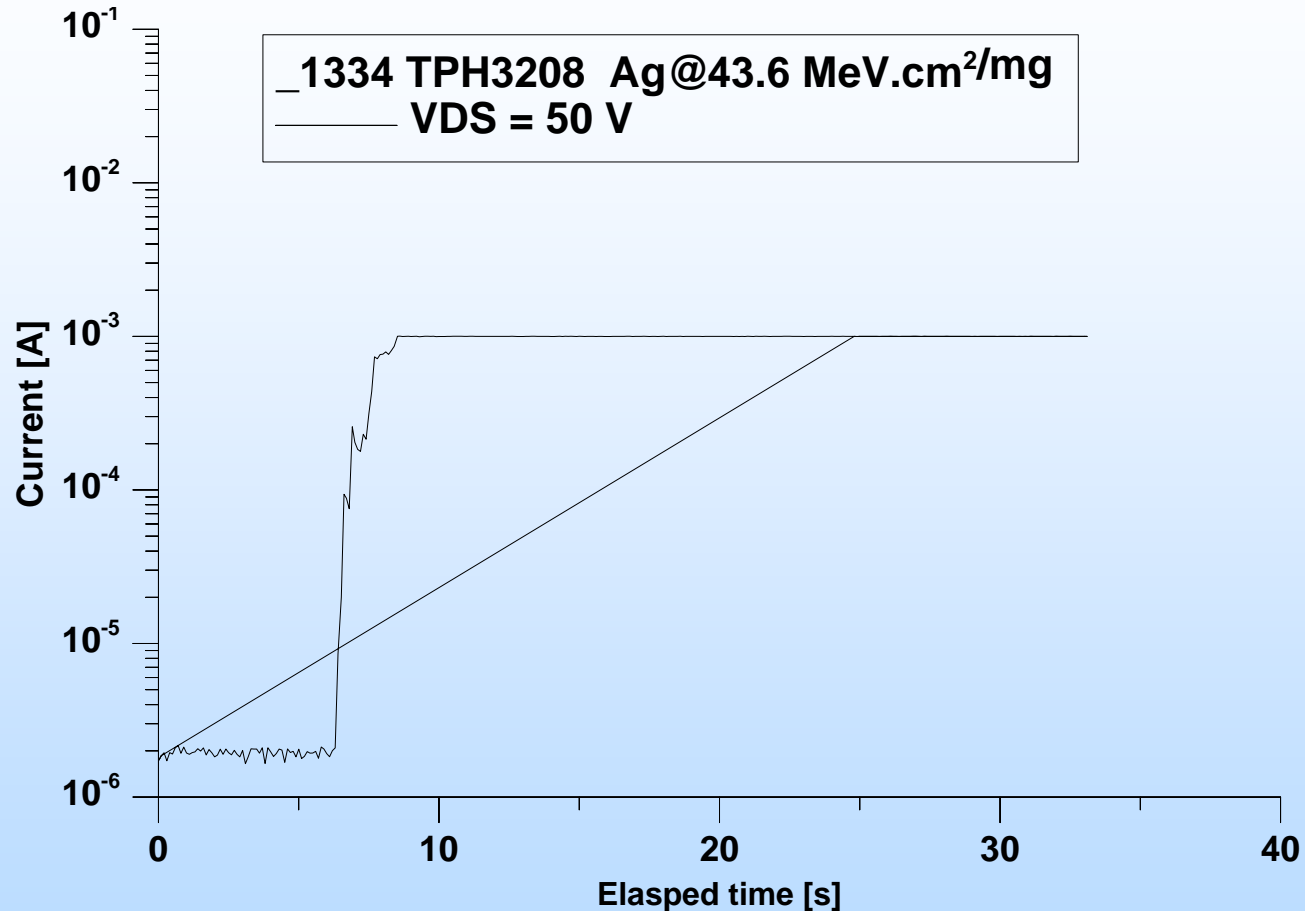


TPS3202
Gate Source Drain



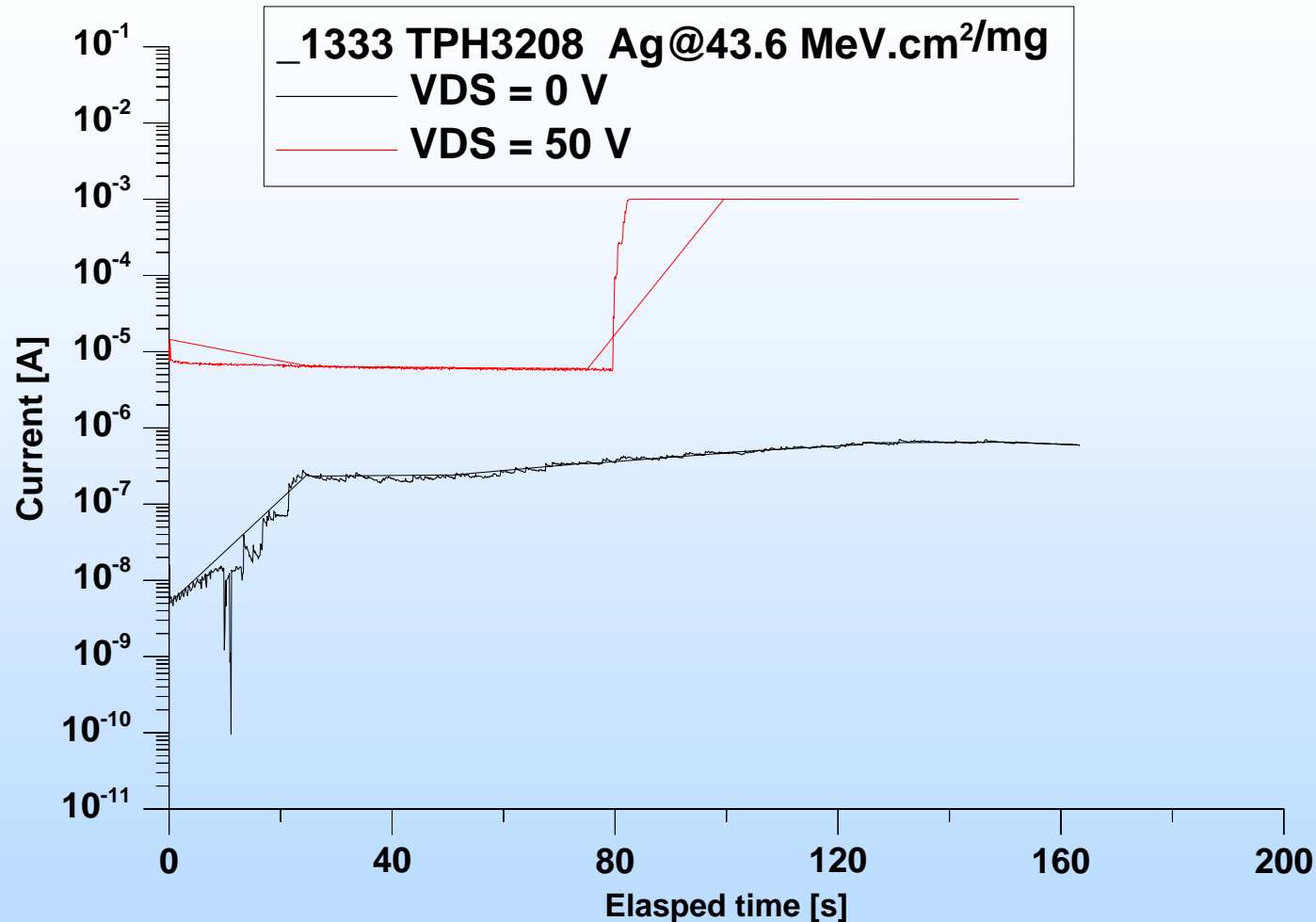
TPH3208
Gate Source Drain

Heavy Ion Testing



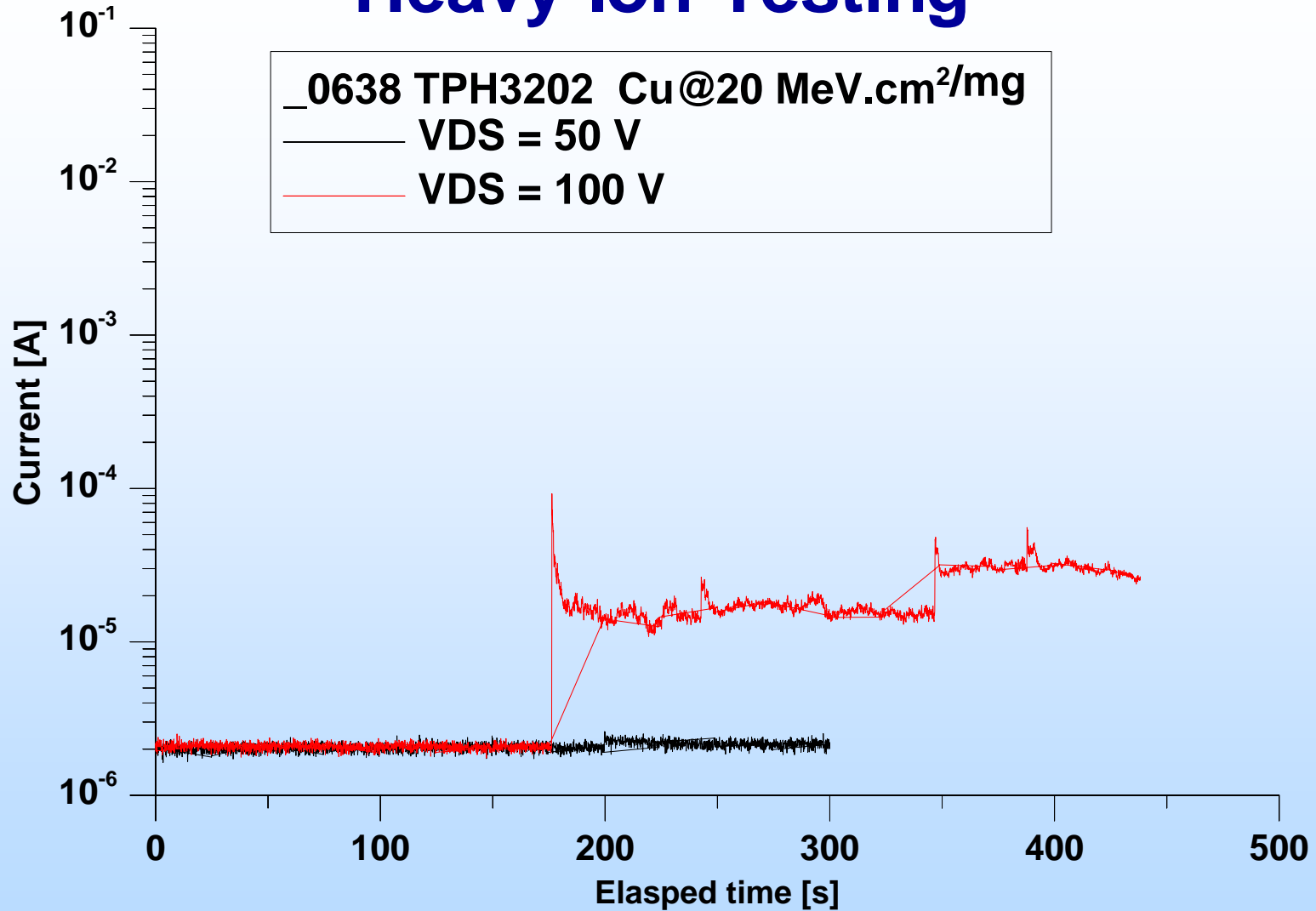
These devices are very soft to ion damage

Heavy Ion Testing



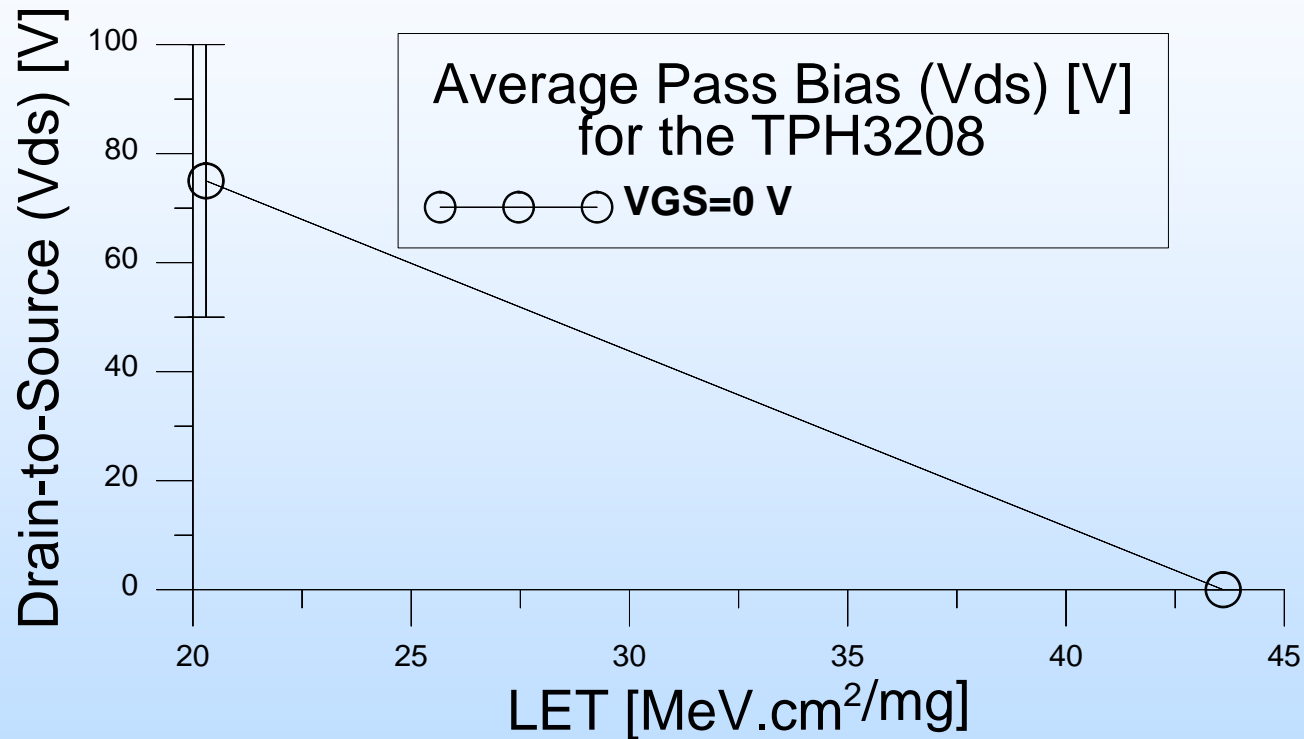
Ions cause damage when unbiased

Heavy Ion Testing



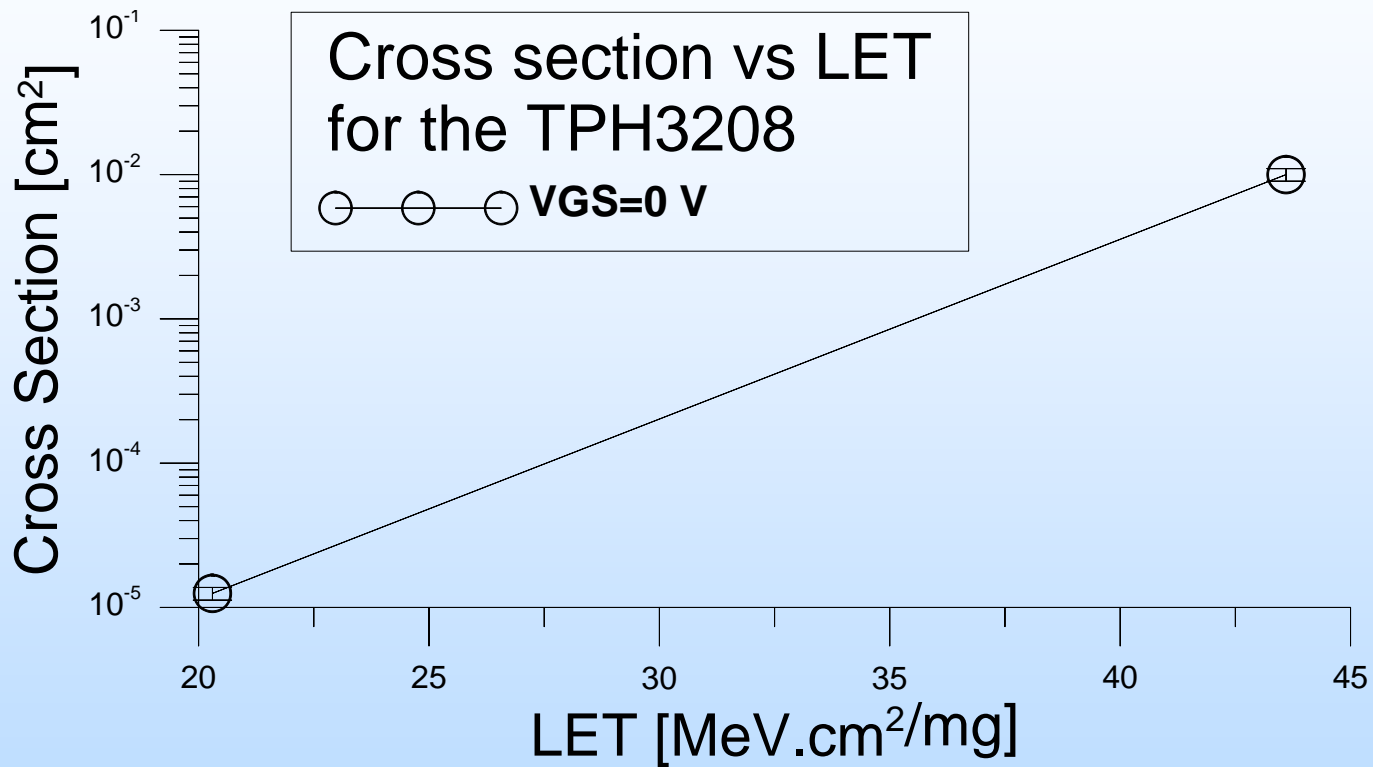
No incremental damage was seen

V_{SEE} as a function of LET



V_{see} is essentially 0 V due to ion incremental damage

Cross-section as a function of LET



Cross-section is dependent on LET

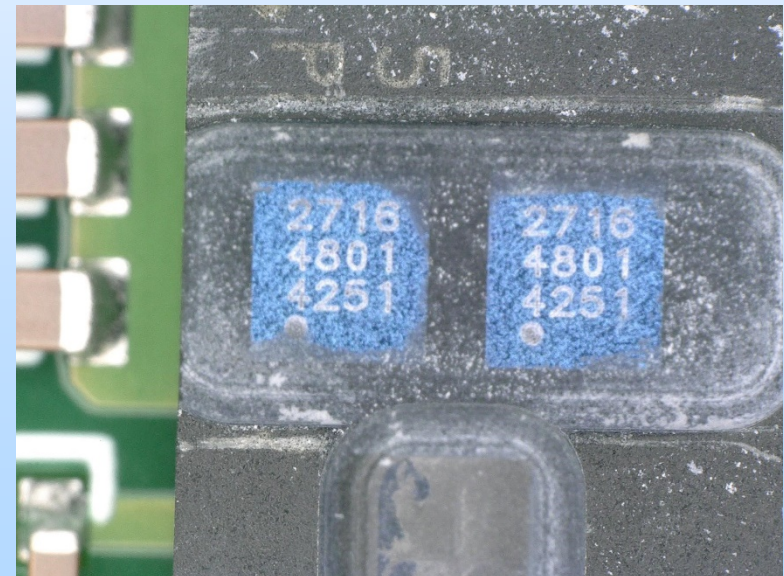
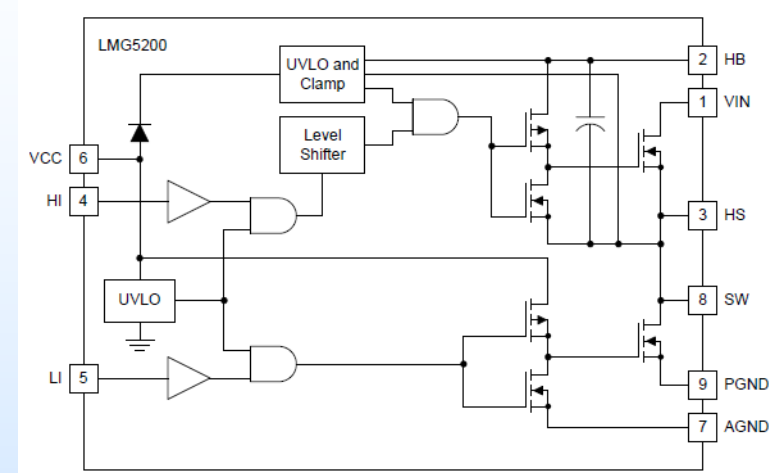


LMG5200

TESTING OF TI HYBRID POWER CONVERTER

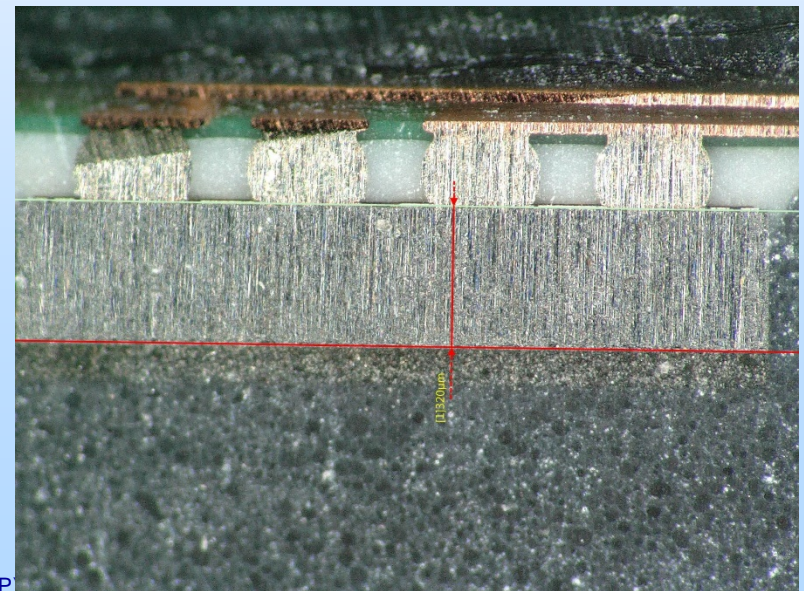
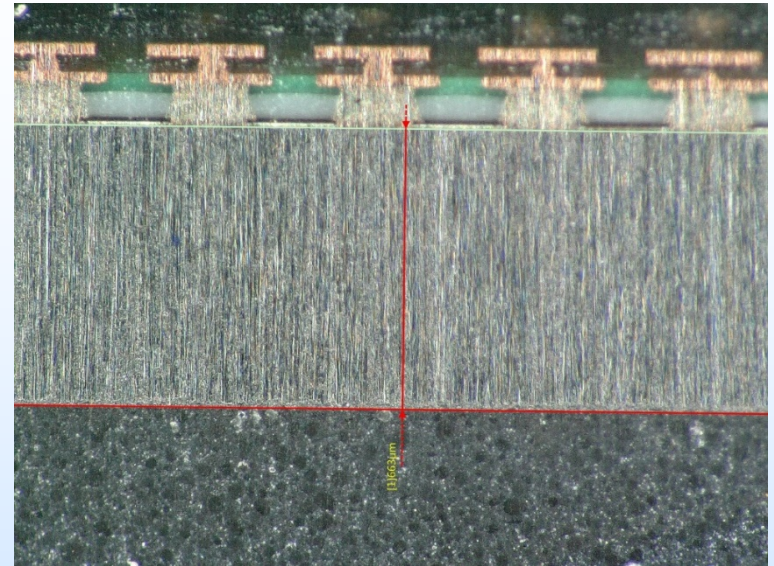
LMG5200

- Texas Instrument's LMG2500 is a Half-Bridge Power Stage
- Needs a PWM on the inputs to operate at a power converter
- Use two 80V enhancement mode GaN HEMTs for switches



LMG5200

- GaN HEMTs had to be milled down for ion penetration
- SEB type failure seen with Kr at 36.3 MeV-cm²/mg with $V_{in} > 70$ V
- SET on the gate maybe the cause
- Piece-part testing is planned

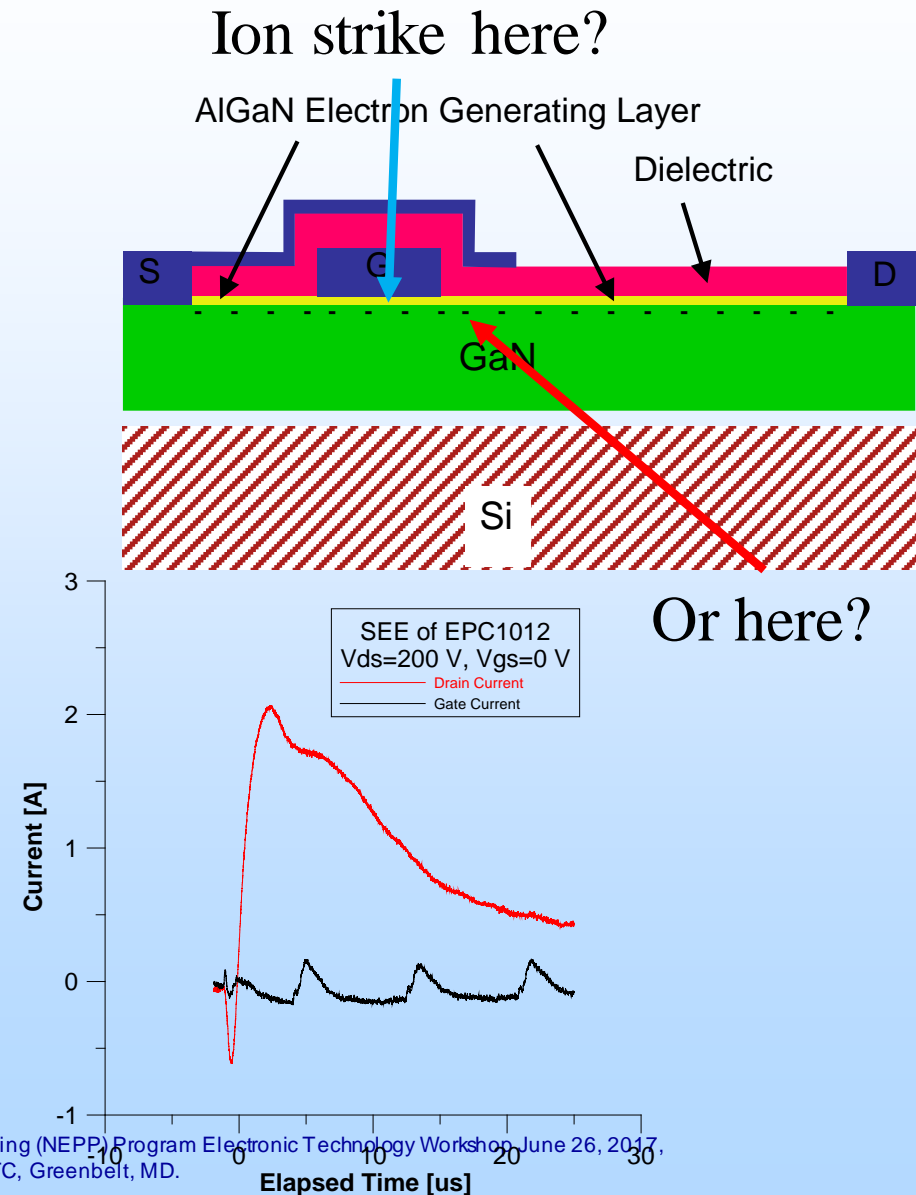




FUTURE WORK

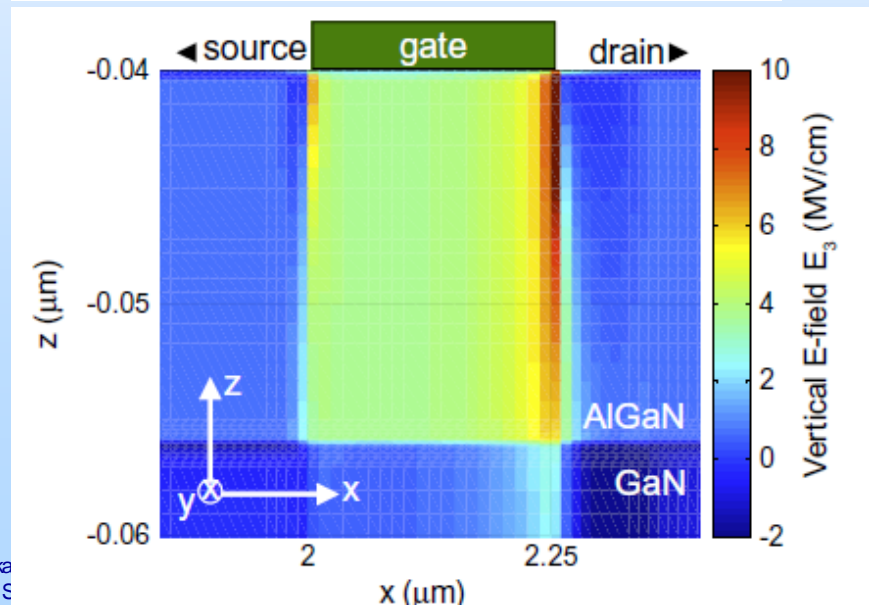
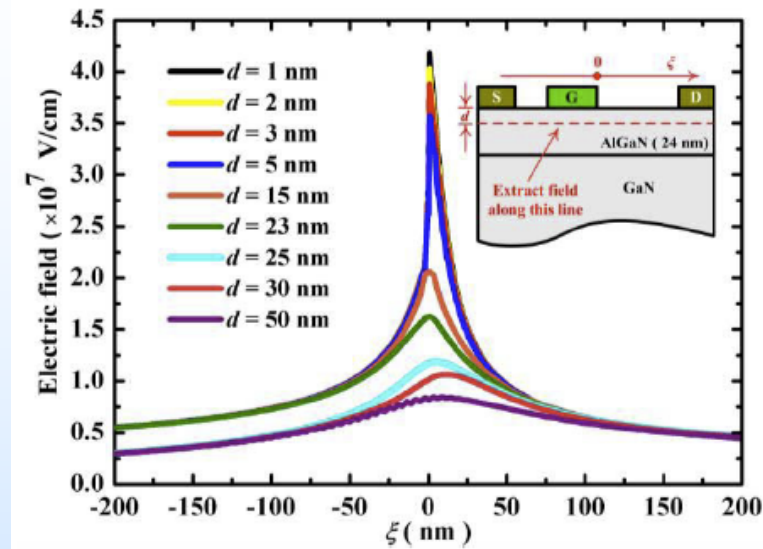
SEE Mechanism

- Since this effect is voltage dependent, we look to the spot with the largest electric field
- This is under the drain side of the gate
- A gate transient occur before an SEE



SEE Mechanism

- The electric field magnitude extends into the GaN substrate
- Very narrow region of very high field
- Resulting strain on junction will make it easier to have SEE





More testing

- **Panasonic parts**
 - Best vehicle for mechanism investigation
- **Transphorm**
 - They are so soft, may also yield mechanism clue
- **TI parts**
 - TPS53632G and LMG3410 are on deck for SEE
- **Freebird Semi**
 - Resping of EPC product line – include higher voltage parts – worth another look



Conclusion

- **SEE in GaN HEMTs are complex**
 - Mechanisms and underlying device physics are still under study
- **New devices show similar effects**
 - Panasonic parts seem more robust
 - Transphorm devices show that GaN can be very soft and there is no natural low voltage threshold
- **Future plans**
 - Body of Knowledge document with GRC
 - Testing guideline in works
 - Collaborate with NASA flight projects and external customers